AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

1-32. (Canceled)

33. (Previously Presented) A substrate processing system comprising:

a plurality of modules whereupon a substrate is transferred into and out of said modules;

a substrate transfer mechanism which transfers the substrate between said modules; and

a control section which controls the substrate transfer mechanism to transfer a first lot of substrates and a second lot of substrates with a first transfer flow and a second transfer flow, respectively, said first transfer flow and said second transfer flow are different from each other relative to said modules, said first lot of substrates being processed before said second lot of substrates,

wherein the control section includes:

a first function of forming a transfer control table formed of a two-dimensional table defined by a transfer flow axis denoting said modules as a row and a time axis denoting transfer timings of the substrate relative to said modules, said first function is preset to regard, as cells, intersection points each specified by one of said transfer timings and one of said modules on said transfer control table, and to correlate the cells with substrate identification information to generate a first transfer schedule of said first lot of substrates and a second transfer schedule of said second lot of substrates,

a second function of modifying said second control transfer schedule by use of said transfer control table, said second function is preset to recognize a first cell group of cells defining said first transfer schedule as a first figure and a second cell group of cells defining said second transfer schedule as a second figure on said transfer control table, and to shift said second figure toward said first figure along the time axis to modify said second transfer schedule within a range in which said second figure does not interfere with said first figure, and

a third function of controlling said substrate transfer mechanism to transfer said first lot of substrates and said second lot of substrates in accordance with said first transfer schedule and said second transfer schedule.

34. (Previously Presented) The substrate processing system according to claim 33, wherein said second function is preset to shift said second figure toward said first figure along the time axis until a front side of said second figure comes into contact with said first figure.

35. (Withdrawn) The substrate processing system according to claim 33, wherein said second function is preset to shift said second figure toward said first figure along the time axis without deforming said second figure.

36. (Withdrawn) The substrate processing system according to claim 33, wherein said modules include process modules.

37. (Withdrawn) The substrate processing system according to claim 36, wherein said process modules are configured to perform resist coating, development after resist exposure, hydrophobic processing of semiconductor substrates, heating and cooling.

38. (New) The substrate processing system according to claim 33, wherein the second function is preset to shift the second figure toward the first figure along the time axis without deforming the second figure until a front side of the second figure comes into contact with the first figure.